Notice of Allowability	Application No.		Applicant(s)	
	10/596,450		PAWLAK ET AL.	
	Examiner		Art Unit	
	David Nhu		2818	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address—All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
1. This communication is responsive to <u>12/3/07</u> .		••	•	
2. The allowed claim(s) is/are <u>1-9</u> .				
 3. Acknowledgment is made of a claim for foreign priority una a) All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of the priority unapplication of the priority documents have	been received. been received in Applic cuments have been rece	ation No lived in this r	national stage applica	
noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.				
 CORRECTED DRAWINGS (as "replacement sheets") mus (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the 	t be submitted. on's Patent Drawing Re Amendment / Commen	view (PTO-9	948) attached ffice action of gs in the front (not the	e back) of
 DEPOSIT OF and/or INFORMATION about the depos attached Examiner's comment regarding REQUIREMENT F 	sit of BIOLOGICAL MA FOR THE DEPOSIT OF	ATERIAL m BIOLOGICA	nust be submitted. I LL MATERIAL.	Note the
Attachment(s)				
1. Notice of References Cited (PTO-892)			itent Application	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interviev Paper N	v Summary (No./Mail Date	P10-413),	
Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	7. 🗌 Examine	er's Amendm	ent/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examine 9. □ Other _	er's Statemer	nt of Reasons for Allo	owance
		- En		

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REASONS FOR ALLOWANCE

- 1. Claims 1-9 are allowed.
- 2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claim 1: wherein a pocket region of the second conductivity type and with a doping concentration higher than the doping concentration of the channel region is formed below the extension, and wherein the pocket region is formed by implanting heavy ions in the semiconductor body, after which implantation, a first annealing process is done at a moderate temperature and a second annealing process with a fast ramp-up is done at a higher temperature, characterized in that between the two annealing processes, amorphous silicon in the semiconductor body is intentionally kept present in a surface region of the semiconductor body which extends from the surface of the semiconductor body up to about a projected range of the implanted pocket region.
- 3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Milic-Strkalj et al (6,080,630): Method for Forming a MOS Device Self-Compensating Vt Implants.

Noda et al 96,432,802 B1): Method for Fabricating Semiconductor Device.

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5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792.

The examiner can normally be reached on Monday-Friday from 7:00 AM to 5:30 PM.

The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.

David Nhu 3

December 17, 2007